

**COPOLYESTER AND ITS MANUFACTURING METHOD**

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**Abstract**

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**PROBLEM TO BE SOLVED:** To provide a copolyester and its manufacturing method suitable for a container or the like having gas barrier property, having high molecular weight and excellent in impact resistance, good in transparency and low in generation of a cyclic oligomer.

**SOLUTION:** This copolyester comprises acid components comprising isophthalic acid, terephthalic acid and an alkali metal salt of 5-sulfoisophthalic acid or an alkali earth metal salt of 5-sulfoisophthalic acid, and their mole ratio satisfies a specific formula and ethylene glycol and including copolymerized phosphorus compounds in amount of  $1 \times 10^{-4}$ - $200 \times 10^{-4}$  mole per mole of the acid components, and the solution haze of the copolyester is  $\leq 15\%$  and number average molecular weight  $\geq 10,000$ .

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